

Application/Control No.	Applicant(s)/Patent under Reexamination	
10/699,613	DELEULE, ARNAUD	
Examiner	Art Unit	
Phallaka Kik	2825	

	SEARCHED				
Class	Subclass	Date	Examiner		
716	10,19	11/1/2005	PK		
700	116,221	11/1/2005	PK		
700	225	11/1/2005	PK		
326	38,41,47	11/1/2005	PK		
326	101	11/1/2005	PK		
Above	updated	2/28/2006	PK		
Above	new	2/28/2006	PK		
700	115	2/28/2006	PK		
257	758	2/28/2006	PK		

INTERFERENCE SEARCHED				
Class	Subclass	Date	Examiner	
716	10,19	2/28/2006	PK	
700	115	2/28/2006	PK	
257	758	2/28/2006	PK	
USPGPUB (see attached)		2/28/2006	PK	

SEARCH NOT (INCLUDING SEARCH)
	DATE	EXMR
BRS (EAST)USPAT, USPGPUB Cls/Sub searched: 716/1-21; 700/115- 116,221-222,224-227; 326/38-50,101- 103; 438/6-10 (see attach)	11/1/2005	PK
Above updated and new searchadditional cls/sub searched: 257/758,620,754.e23.179; 700/97,121 (see attached)	2/28/2006	PK
-EPO, JPO, IBM TDB, Derwent (see attached)	11/1/2005	PK
Consulted with Examiner Khoi Tran on similar case -no need to cross-reference to 700/213+	11/1/2005	PK
Consulted with Examiner Vibol Tan -no search or cross-referencing to class 326 is needed. Suggested search in class 257.	2/27/2006	PK
Consulted with Examiner Nathan W. Ha suggested search and cross- referencing to 257/758	2/26/2006	PK
Consulted with Examiner Sean Shechtman on similar case -suggested search and cross- referencing to 700/115	2/23/2006	PK
IEE/IEEE Xplore (see attached)	11/1/2005	PK